

Amendments to the Claims:

The following listing of claims will replace all prior versions, and listings, of claims in the application:

1. (Currently Amended) A sol in which particles are dispersed in a medium, wherein the particles have a particle size of ~~0.005 to 1 μ m~~ 50 to 150 nm and comprise as a main component crystalline cerium oxide of the cubic system and as an additional component a lanthanum compound, neodymium compound or a combination thereof, wherein the additional component is contained in X/(Ce + X) molar ratio of ~~0.001 to 0.50~~ 0.005 to 0.15 in which X is lanthanum atoms, neodymium atoms or a combination thereof.

2. (Original) A sol according to claim 1, wherein the additional component is a lanthanum compound.

3. (Original) A sol according to claim 1, wherein the additional component is a neodymium compound.

4-9. (Canceled)

10. (Currently Amended) An abrasive containing a sol in which particles are dispersed in ~~a~~ an aqueous medium in a range of 0.1 to 50 wt%, wherein the particles have a particle size of ~~0.005 to 1 μ m~~ 50 to 150 nm and comprise as a main component crystalline cerium oxide of the cubic system and as an additional component a lanthanum compound, neodymium compound or a combination thereof, wherein the additional component is contained in X/(Ce + X) molar ratio of ~~0.001 to 0.50~~ 0.005 to 0.15 in which X is lanthanum atoms, neodymium atoms or a combination thereof.

11. (Currently Amended) ~~A~~ A method of making an abrasive containing a sol in which particles are dispersed in a medium, wherein the particles have a particle size of ~~0.005 to 1 μ m~~ 50 to 150 nm and comprise as a main component crystalline cerium oxide of the cubic system and as an additional component a lanthanum compound, neodymium compound or a

combination thereof, wherein the additional component is contained in X/(Ce + X) molar ratio of ~~0.001 to 0.50~~ 0.005 to 0.15 in which X is lanthanum atoms, neodymium atoms or a combination thereof, ~~characterized in that~~ the method comprising producing the sol is produced according to the steps:

a first step of reacting an aqueous solution which a cerium (III) salt is mixed with a lanthanum (III) salt, a neodymium (III) salt or a combination thereof in an aqueous medium in X/(Ce + X) molar ratio of 0.001 to 0.5, with an alkaline substance in (OH⁻)/(Ce³⁺ + X³⁺) molar ~~ratio~~ ratio of 3 to 30 to give a suspension in which cerium (III) hydroxide and a hydroxide of the trivalent additional component X are homogeneously mixed; and

a second step of blowing oxygen or a gas containing oxygen into the suspension at a temperature of 10 to 95°C.

12. (Previously Presented) An abrasive according to claim 10, wherein the additional component is a lanthanum compound.

13. (Previously Presented) An abrasive according to claim 10, wherein the additional component is a neodymium compound.

14. (Previously Presented) An abrasive according to claim 10, which is adjusted with an acidic substance to a pH of 1 to 6.

15. (Previously Presented) An abrasive according to claim 10, which is adjusted with a basic substance to a pH of 8 to 13.

16. (Previously Presented) An abrasive according to claim 10, which is used for polishing a substrate which comprises silica as a main component.

17. (Previously Presented) An abrasive according to claim 10, which is used for polishing a rock crystal, a quartz glass for photomask, a semiconductor device or a hard disk made of glass.

18. (Previously Presented) An abrasive according to claim 10, which is used in a step of polishing an organic film, a step of polishing Inter Layer Dielectric (ILD) or a step of shallow trench isolation, for polishing a semiconductor device.